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## **Amendments to the Specification:**

Please replace the paragraph beginning on line 9 of page 8 as follows:

suitable microwave generator 16 is operatively connected with a surface plane antenna 18 received just above deposition chamber 12. Typically, surface plane antenna 18 is comprised of a metal material having a plurality of microwave transmissive openings 20 formed therein through which microwave energy generated by source 16 passes to within chamber 12, and proximate the surface of substrate 14. The upper wall of chamber 12 over which surface plane antenna 18 is received is also, therefore, provided to be microwave transmissive. Of course, some or all of surface plane antenna 18 could be provided within deposition chamber 12. exemplary preferred spacing from the upper surface of substrate 13 substrate 14 to the lower surface of second antenna 28 surface plane antenna 18 is 65mm. Of course, greater or small spacings can be utilized. In certain situations, spacings considerably less than 65mm might be utilized. Further, in addition to microwave, energy generation is also contemplated in combination with microwave energy generation, and whether within or externally of chamber 12.

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Please amend the paragraph beginning on line 12 of page 20 as follows:

In Fig. 6, plasma generation of the second precursor gas within the chamber occurs from a second applied power level of energy 40 to the chamber which is capable of generating plasma within the chamber. Some steady-state, first-applied power level of such energy is applied to the chamber at some point prior at least point at least prior to applying the second-applied power level of such energy 40. An exemplary steady-state, first-applied power level 62 is depicted in Fig. 6 which is less than second-applied power level 40, with an increasing from first-applied power 62 to second-applied power level 40 occurring along a line 64.